

# Advanced Silicon Devices – Applications and Technology Trends

Gerald Deboy

Winfried Kaindl, Uwe Kirchner, Matteo Kutschak,  
Eric Persson, Michael Treu

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# Content

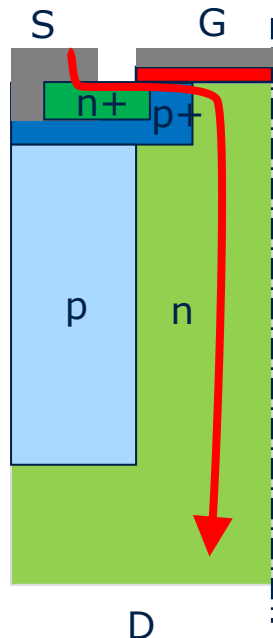
- Silicon devices versus GaN devices: An unbiased view on key performance indicators
- Applications: Comparison of devices in hard-switching and resonant circuits
- Summary

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- Silicon devices versus GaN devices: An unbiased view on key performance indicators
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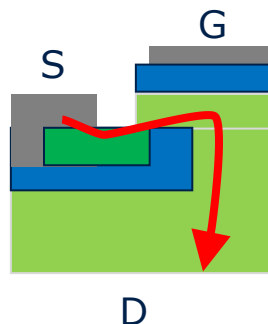
# Comparing competing device concepts

**Si**  
Superjunction



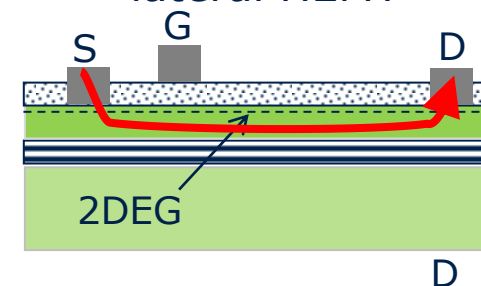
- $R_{ON} \times A$  scales with cell pitch
- Inherently fast switching
- $dv/dt$  scales inversely with cell pitch
- Reverse recovery charge and snappiness of body diode as major drawbacks

**SiC**  
vertical drift zone



- Pitch influences  $R_{ON} \times A$  by improved utilization of the semiconductor volume
- Normally-on; turns into normally-off by Cascode or direct-driven concept
- Good body diode;  $Q_{rr}$  close to SiC Schottky diodes

**GaN**  
lateral HEMT



- Good starting point for low  $R_{ON} \times A$  and  $Q_{OSS}$  due to high electron mobility
- Device capacitances are strongly influenced by the metal re-routing
- Excellent reverse behavior

p-Implantation

p+-Implantation

n+-Implantation

Oxide

n-Epitaxy

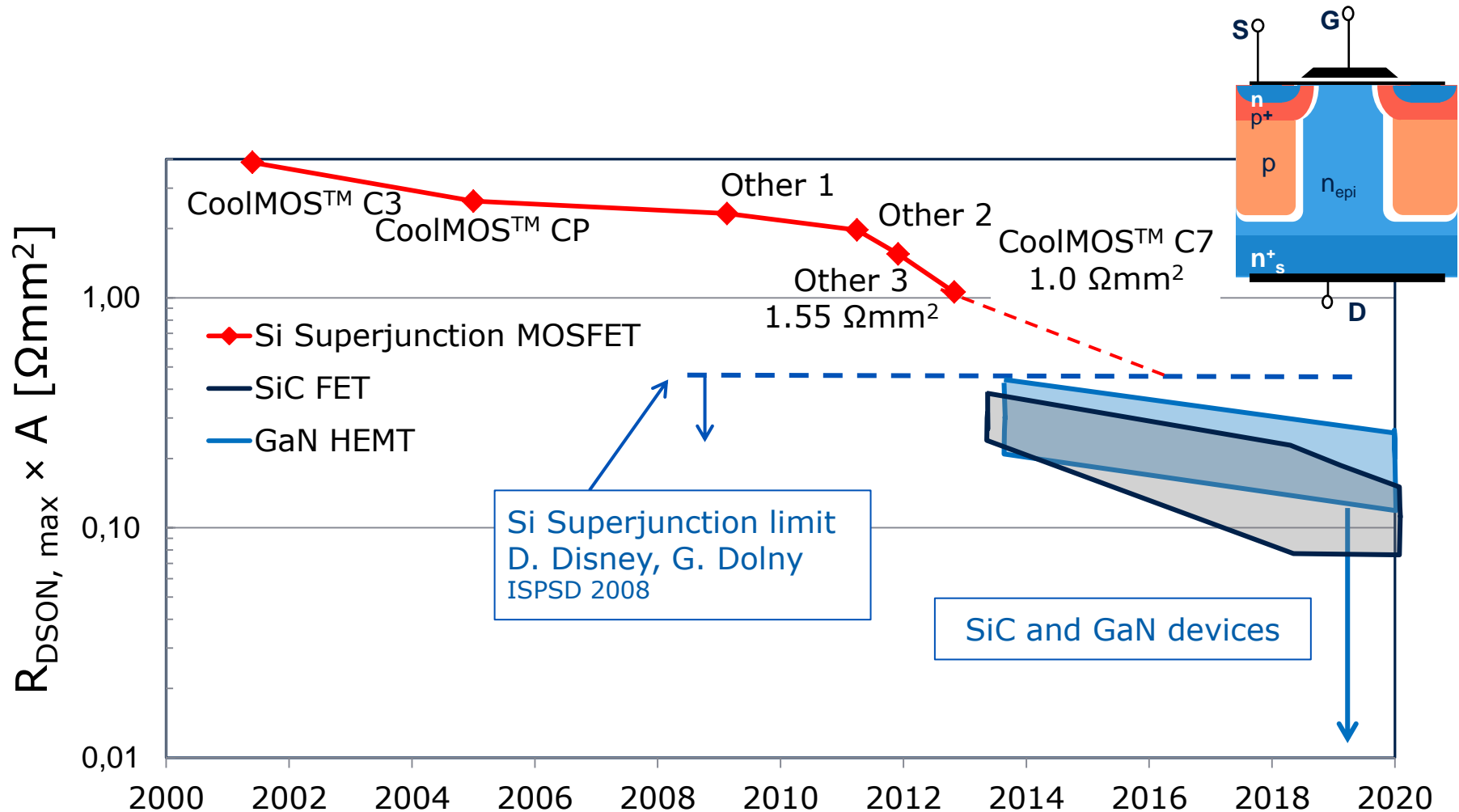
Metal/Poly-Si

AlN/AlGaN Barrier

Si Substrate

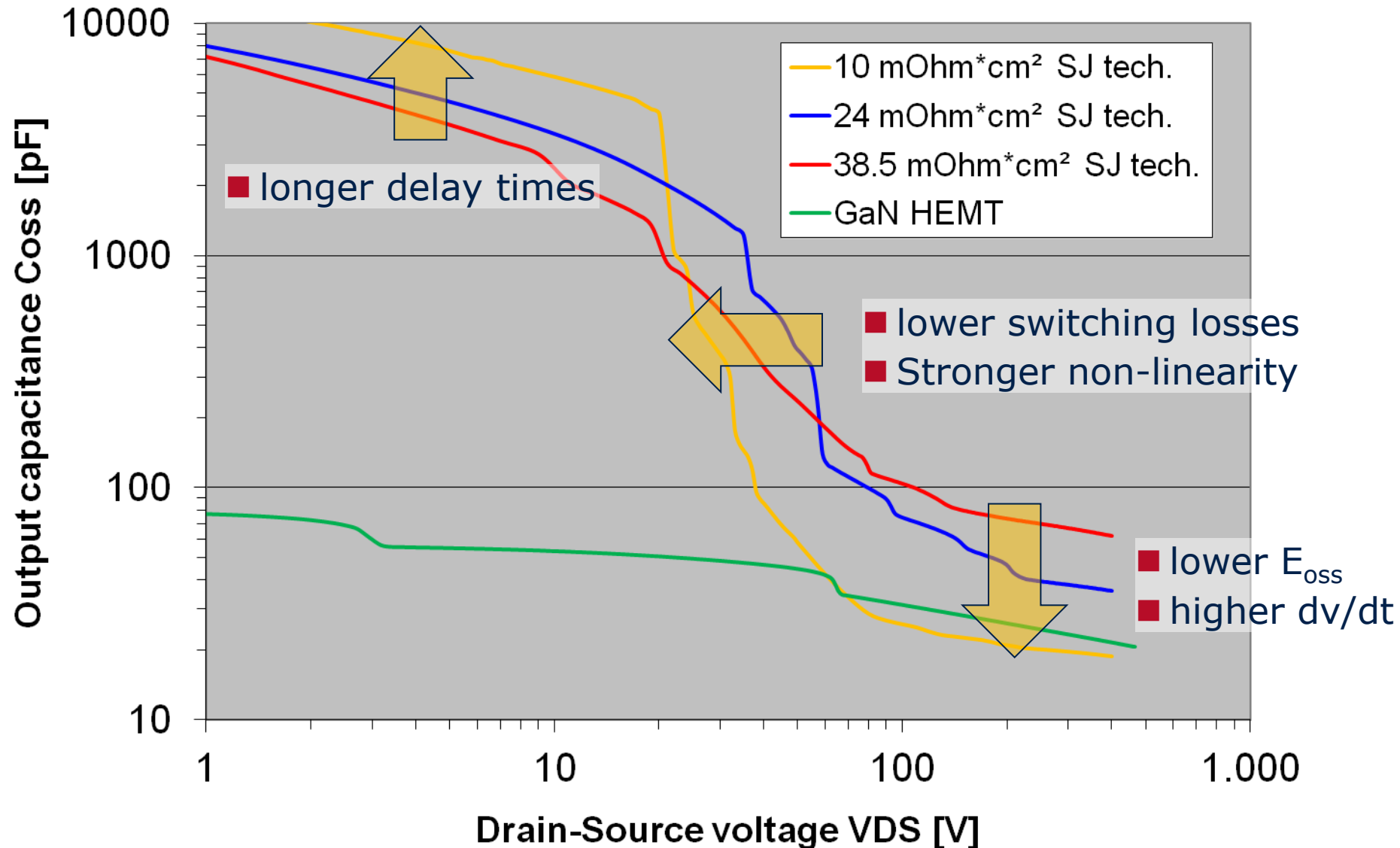
Buffer layer

# How far can the Superjunction concept be exploited in terms of $R_{DSon} \times A$ ?



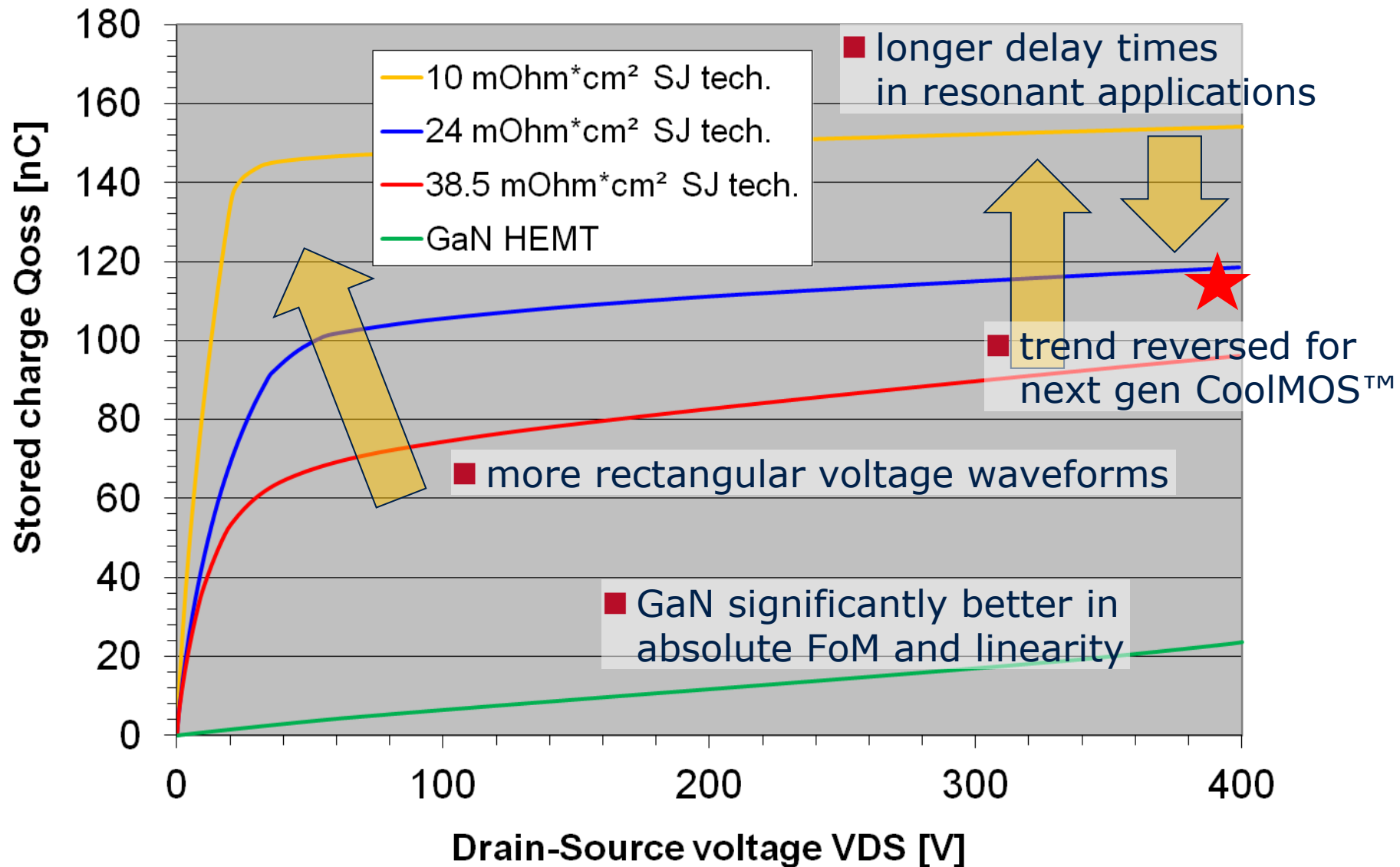
Still a long way until the limit is reached with Si Superjunction.  
Si limit potentially lower than 0.5  $\Omega mm^2$

# The output capacitance of SJ devices gets more non-linear with every generation! 190 mOhm, 600V / 650V devices

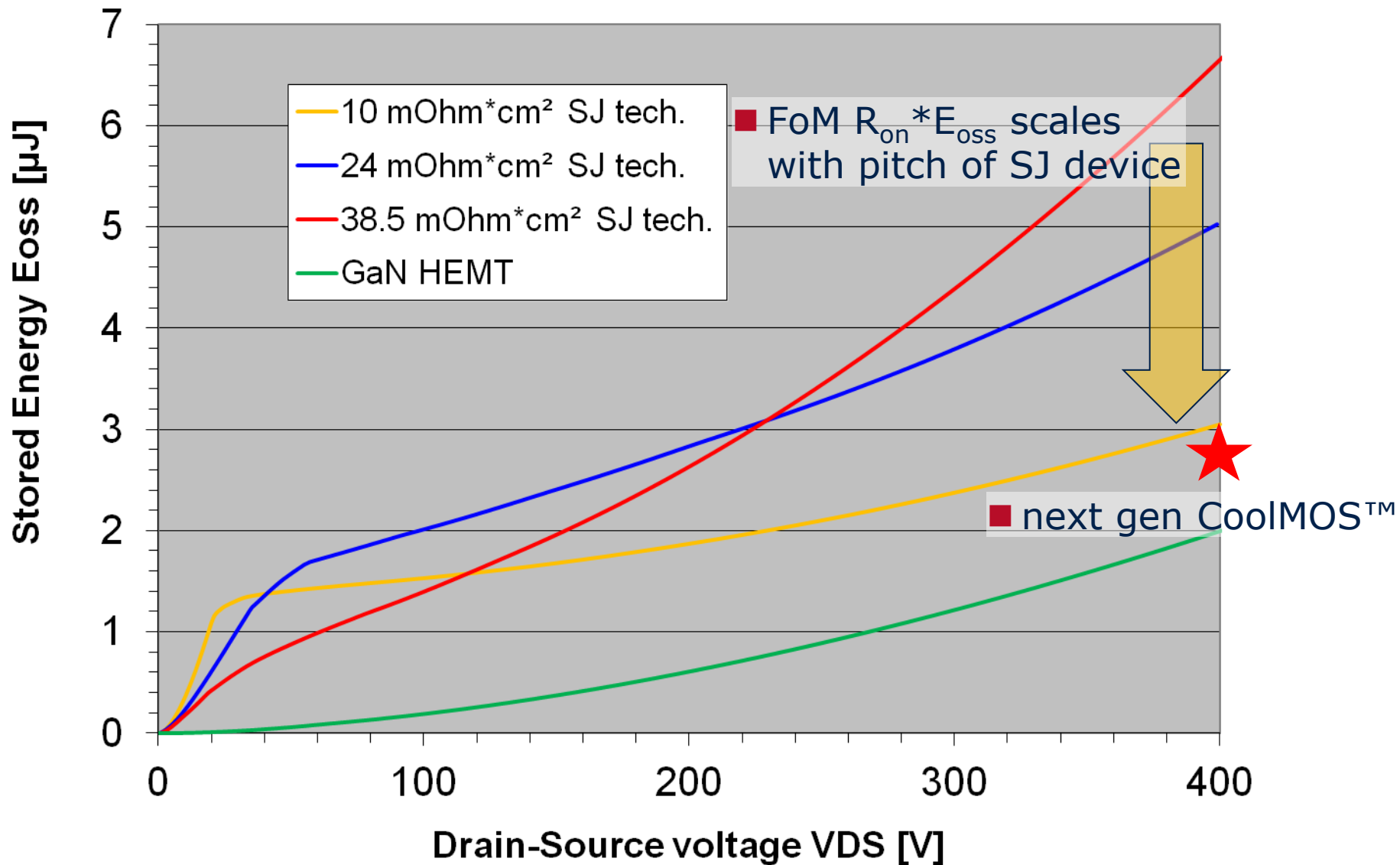


# The $Q_{oss}$ characteristic will become more and more flat!

190 mOhm, 600V / 650V devices

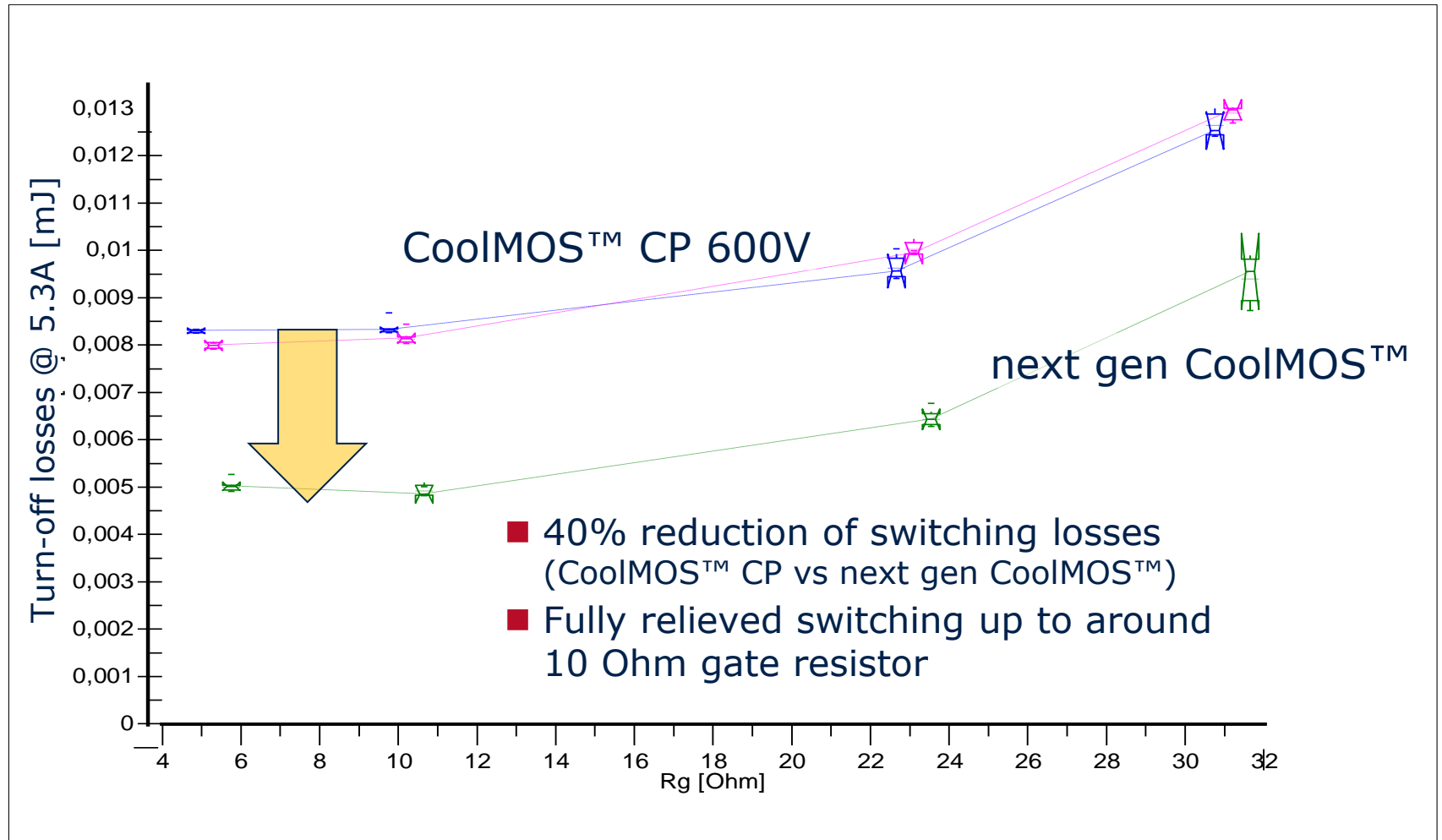


$E_{oss}$  scales with cell pitch and can be brought below the level of 1st gen GaN devices 190 mOhm, 600V / 650V devices

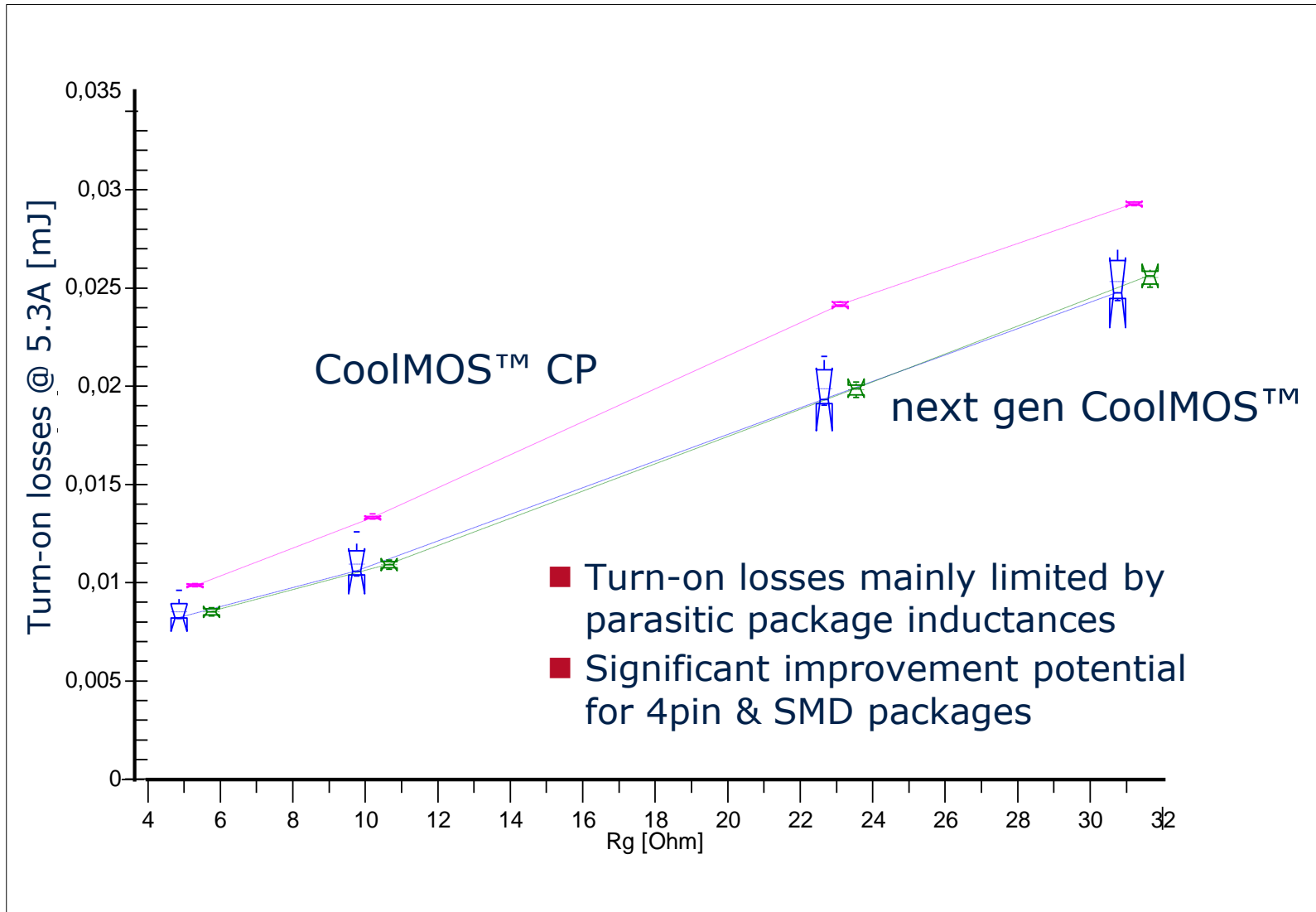




# 40% $E_{oss}$ reduction versus earlier SJ generation fully translates into lower turn-off losses! 190 mOhm / 600V



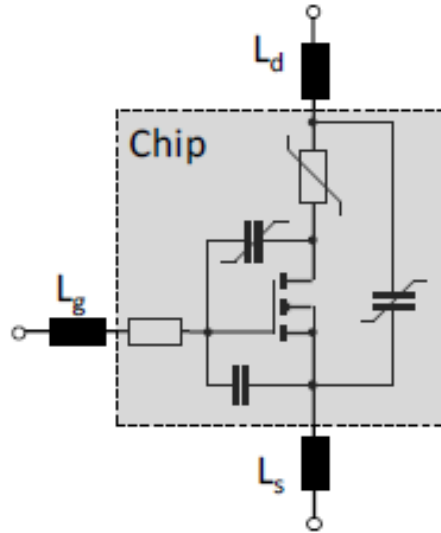
Turn-on losses are mainly determined by package and no longer benefit from silicon improvements! 190 mOhm / 600V



# Package and switching cell optimization are mandatory to fully benefit from fast switching devices!

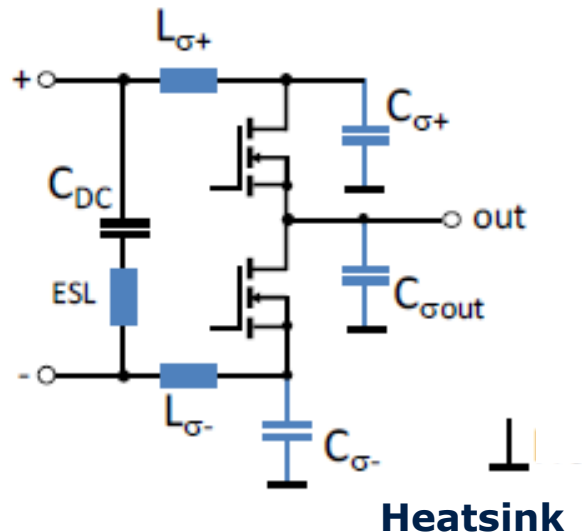
## ■ Package level

- Source inductance most critical
- Solved by Kelvin contact
- however inductance still in the commutation loop



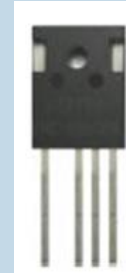
## ■ Switching cell level

- True SMD solution allows compact, low-inductive switching cell
- Symmetric coupling capacitances to heatsink are important from EMI point of view
- Top side cooling optional in DSO-20

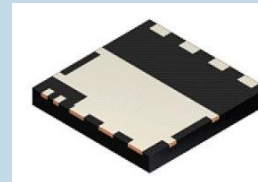


## TO-247 4pin

Kelvin contact to source,  
decoupling of gate drive,  
 $E_{on}$  improvement

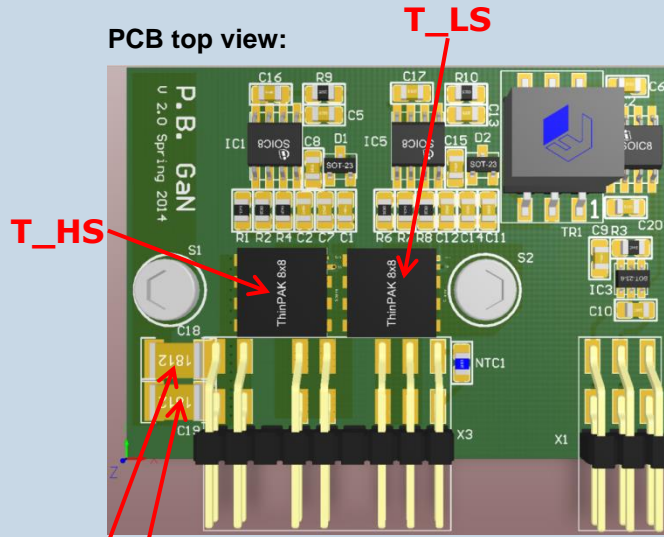


## ThinPAK, TOLL, DSO-20



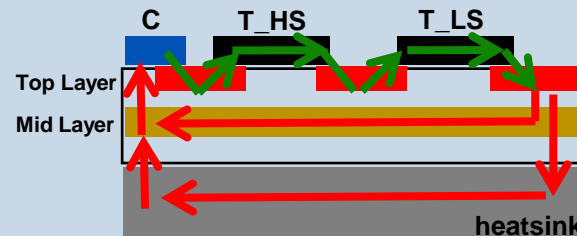
# SMD packages will be important for SJ devices and mandatory for GaN!

PCB top view:



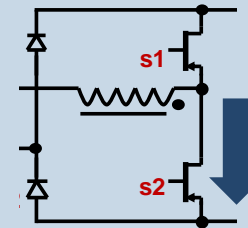
Power loop caps

Current flow:



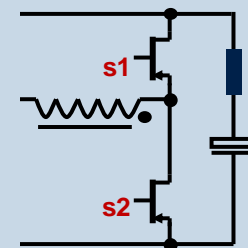
Commutation loop 3.2 nH

## Losses



$$\begin{aligned} C_{\text{heatsink TO}} &= \sim 20 \text{ pF} \\ E_{\text{Cpar}} &= 1.6 \text{ }\mu\text{J} \\ E_{\text{dev}} &= 3 \text{ }\mu\text{J} \end{aligned}$$

## Voltage overshoot

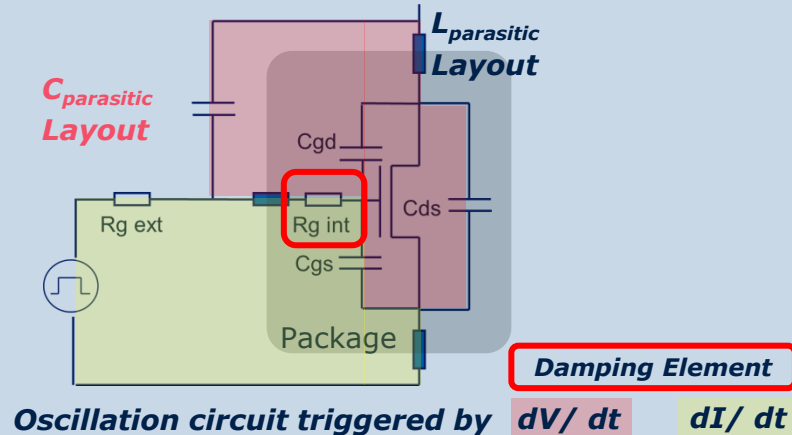


$$\begin{aligned} L_{\text{par TO}} &= \sim 20 \text{ nH} \\ E_{\text{Ipar\_10A}} &= 1 \text{ }\mu\text{J} \\ V_{\text{overshoot}} &= 100\text{V} \\ &\text{@ } 5\text{kA}/\mu\text{s} \end{aligned}$$

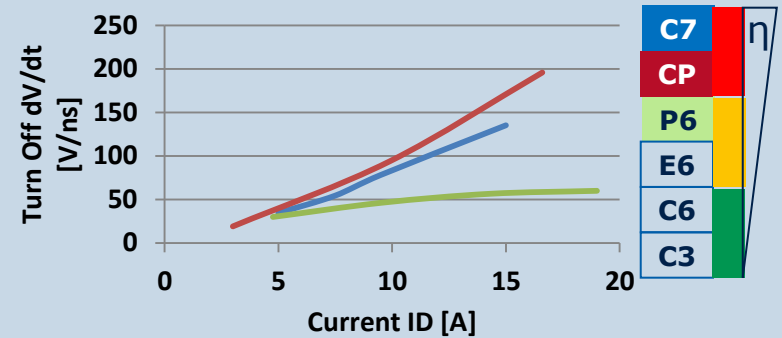
$$L_{\text{par}} = 3\text{--}6 \text{ nH}$$

# In case of layout constraints...

## Possible Ringing Circuit



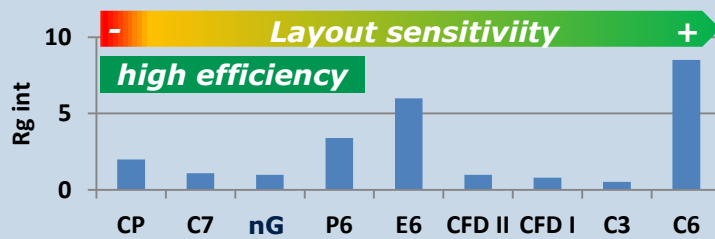
## $dV/dt$



Low switching losses are inevitably coupled to high  $dv/dt$  and  $di/dt$  values both at turn-on and turn-off.

## Layout Sensitivity

- With C6 a integrated Gate Resistor was introduced to damp Oscillations
- Optimization tradeoff efficiency and Layout with each new technology



## How to use fast switching SJ devices

- Avoid a coupling capacitance between G,D
- Place the gate resistor close to the gate
- Avoid Stray inductance in the Power Loop
- Use the mutual inductance effect (opposite current flow, forced current) in the power loop



- Add ferrite beads if necessary

Best performance

Cost/performance segment

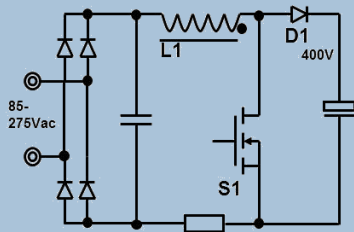
Ease of Use optimized

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# SJ devices will prevail in classic and dual boost GaN offers significant value in Totem Pole PFC

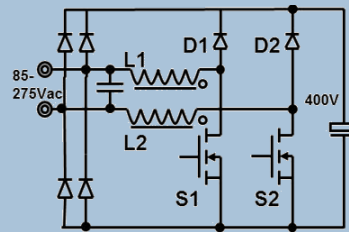
## Classic PFC



- Less System Cost
- Less Efficiency
- High Power Density

- Superjunction (S1)
- SiC (D1)

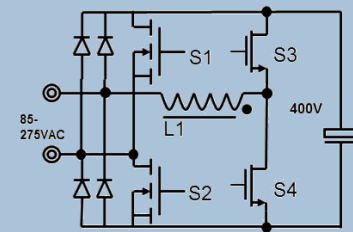
## Dual Boost PFC



- High System Cost
- High Efficiency
- Less Power Density

- Superjunction (S1, S2)
- SiC (D1, D2)

## Totem Pole PFC

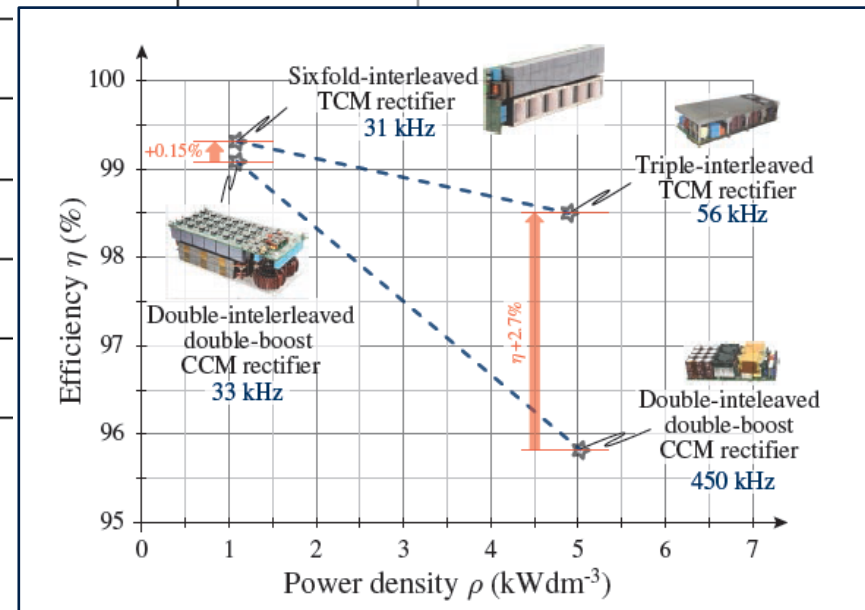
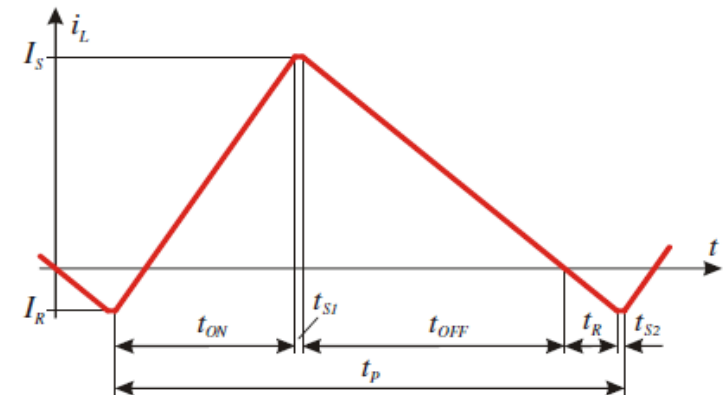
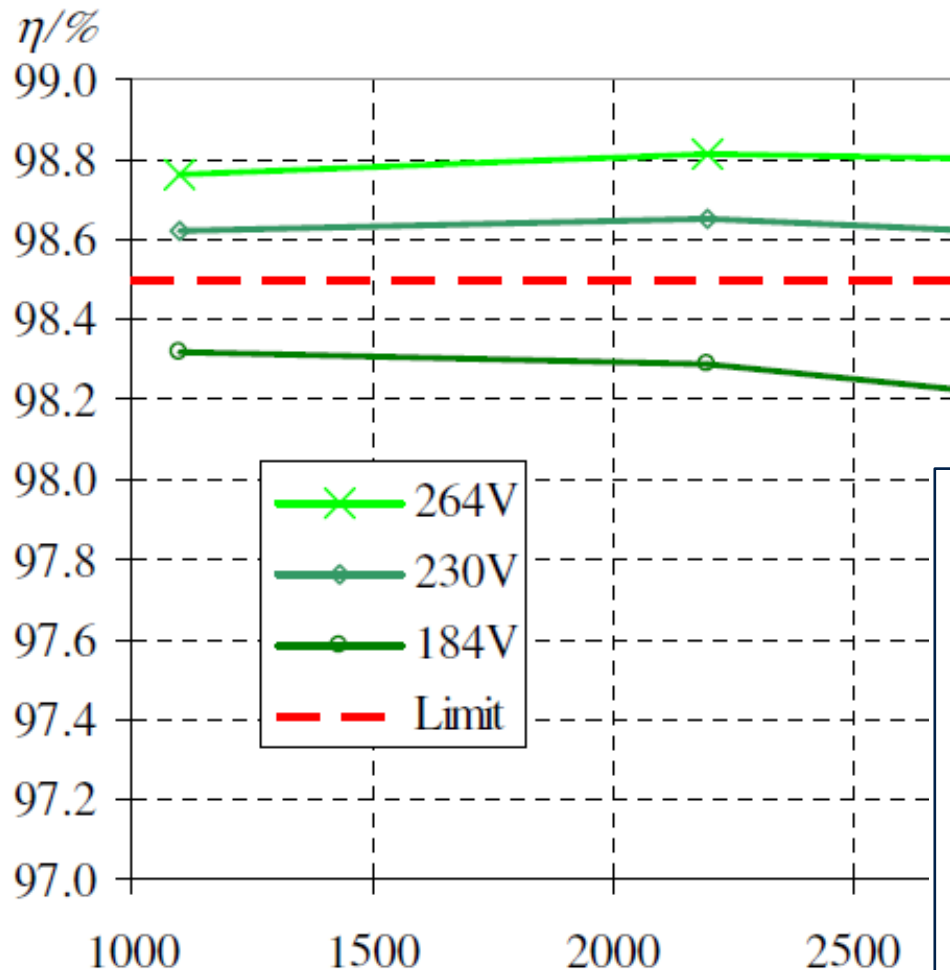


- Less System Cost
- High Efficiency
- High Power Density

- Superjunction (S1, S2)
- GaN, SJ, IGBT (S3, S4)

GaN enables hard  
commutation on  
internal "diode"

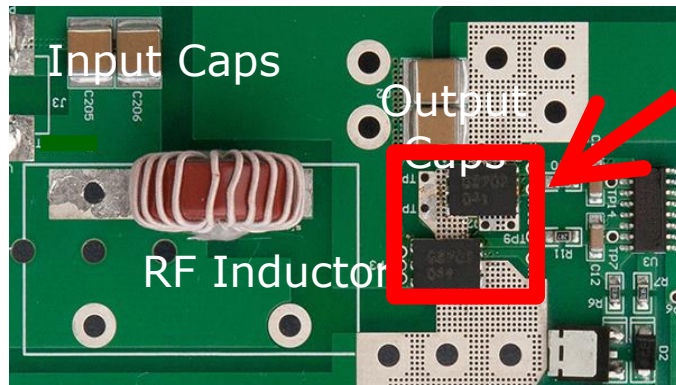
# Best competing silicon alternative in terms of power density and efficiency: TCM PFC 3 kW, 4.5 kW/l (74W/in<sup>3</sup>)



Source: U. Badstübner, J. Miniböck, J. Kolar, „ Experimental Verification of the Efficiency/Power-Density (n-p) Pareto Front of Single-Phase Double-Boost and TCM PFC Rectifier Systems“, Proc. APEC 2013.



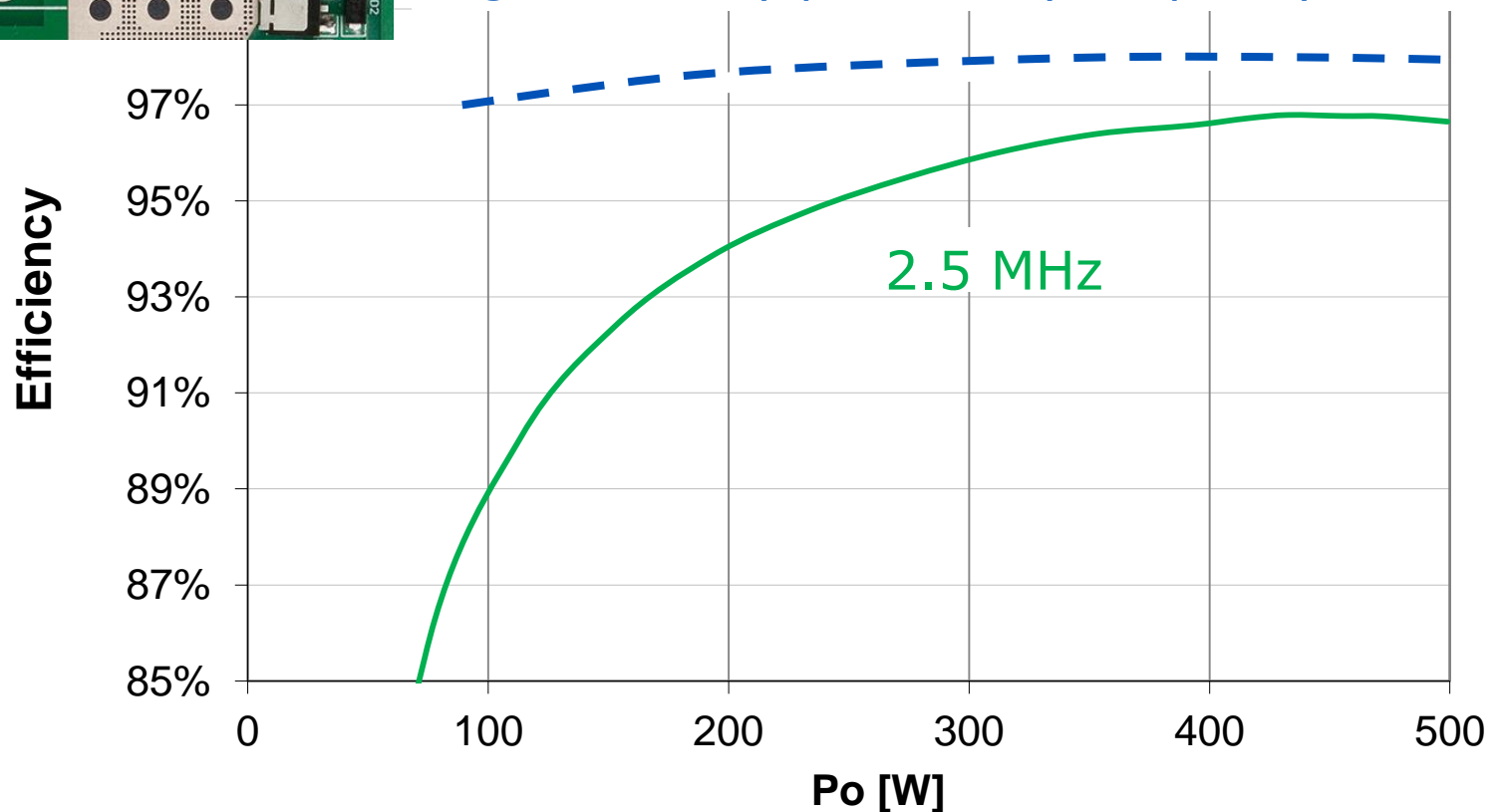
# Advantage of GaN: very high frequency operation with $R_{on} * Q_{oss}$ and $Q_g$ as key parameters



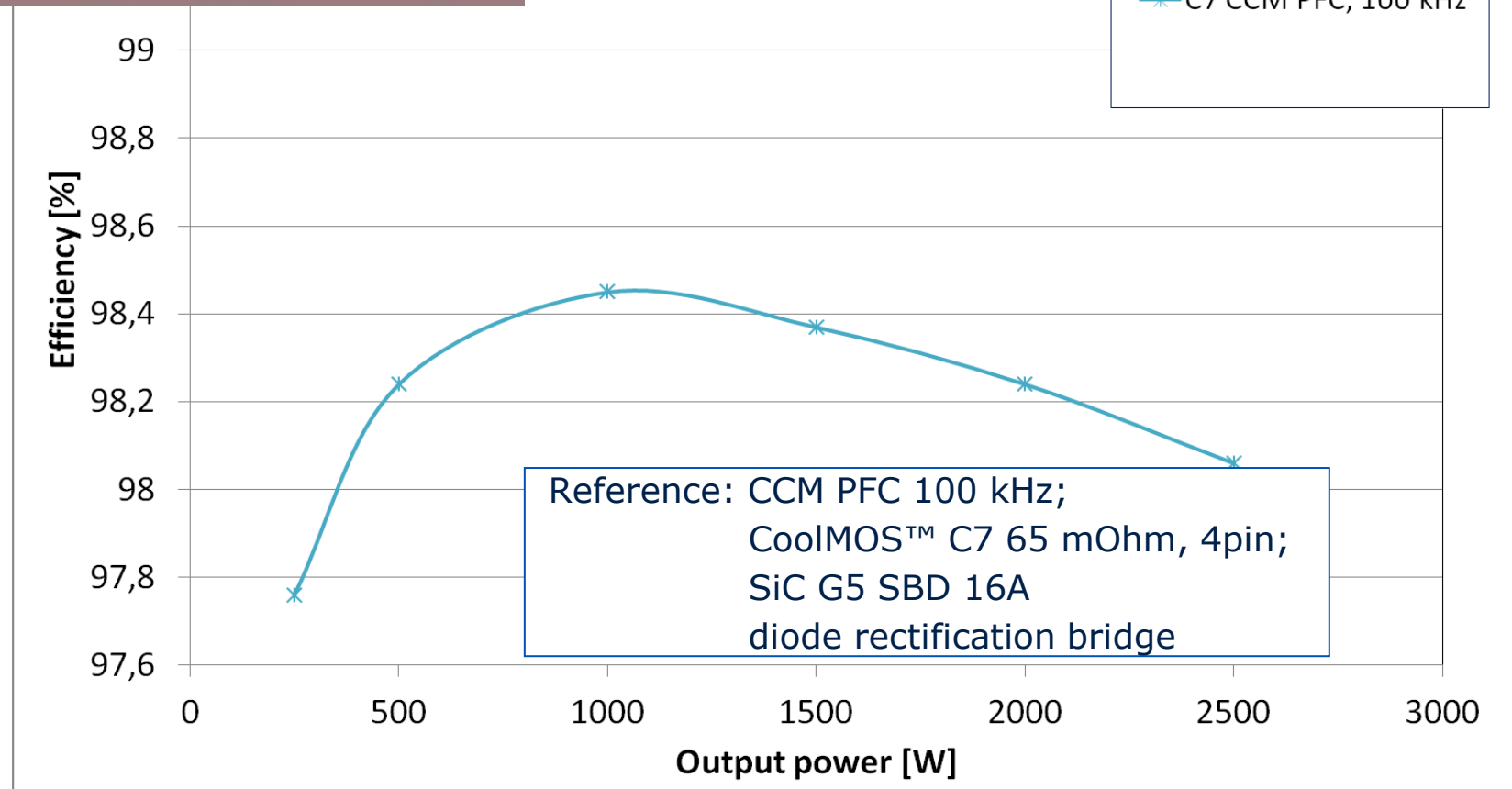
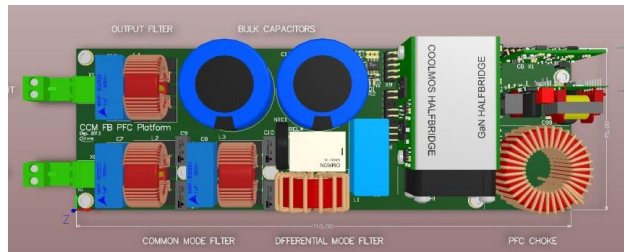
GaN Switches

Gate Driver

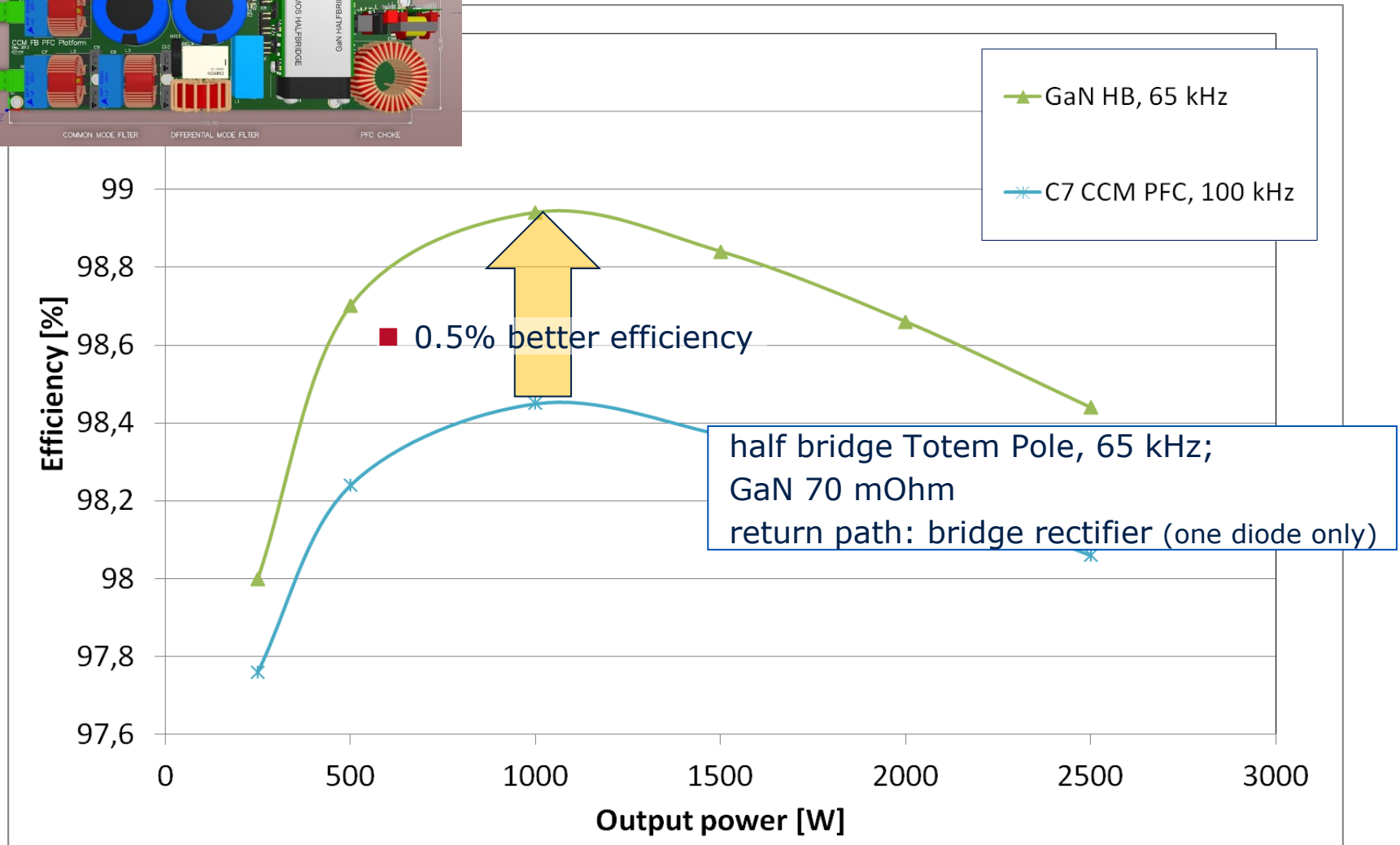
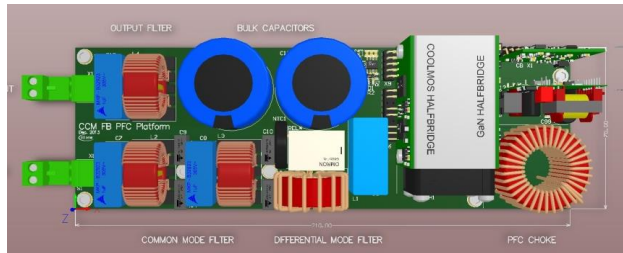
High efficiency possible by frequency control



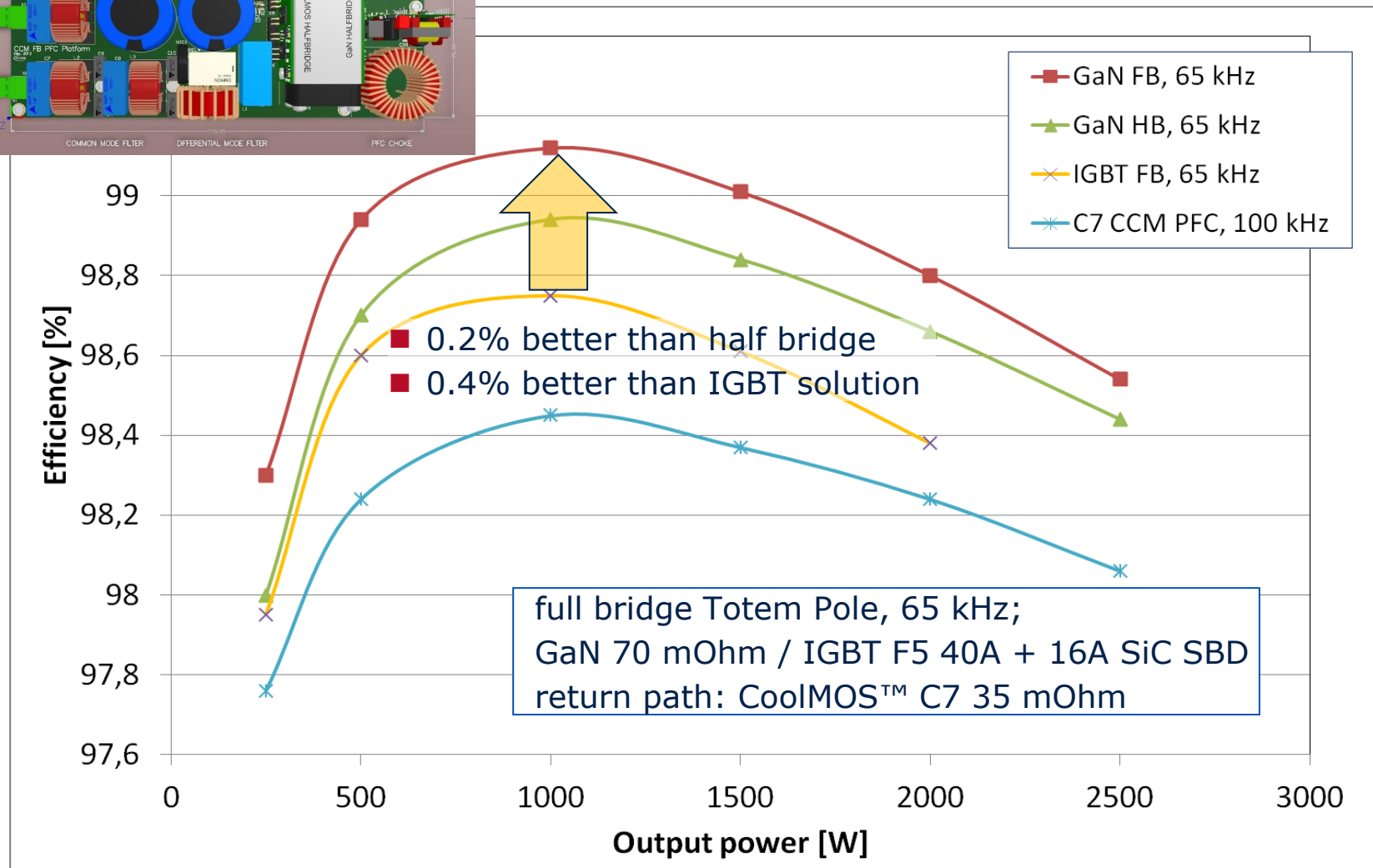
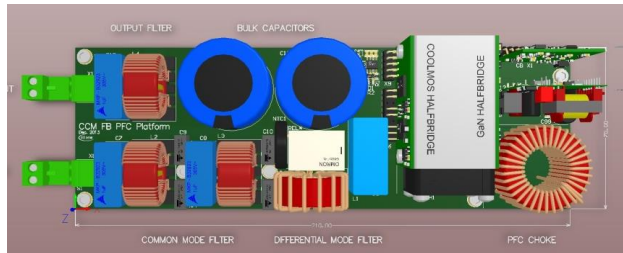
# Comparison of hard-switching PFC stages: Reference: CoolMOS™ C7 / SiC G5



# Advantage of GaN: CCM modulation in Totem Pole PFC, close to 99% efficiency with simple half bridge solution

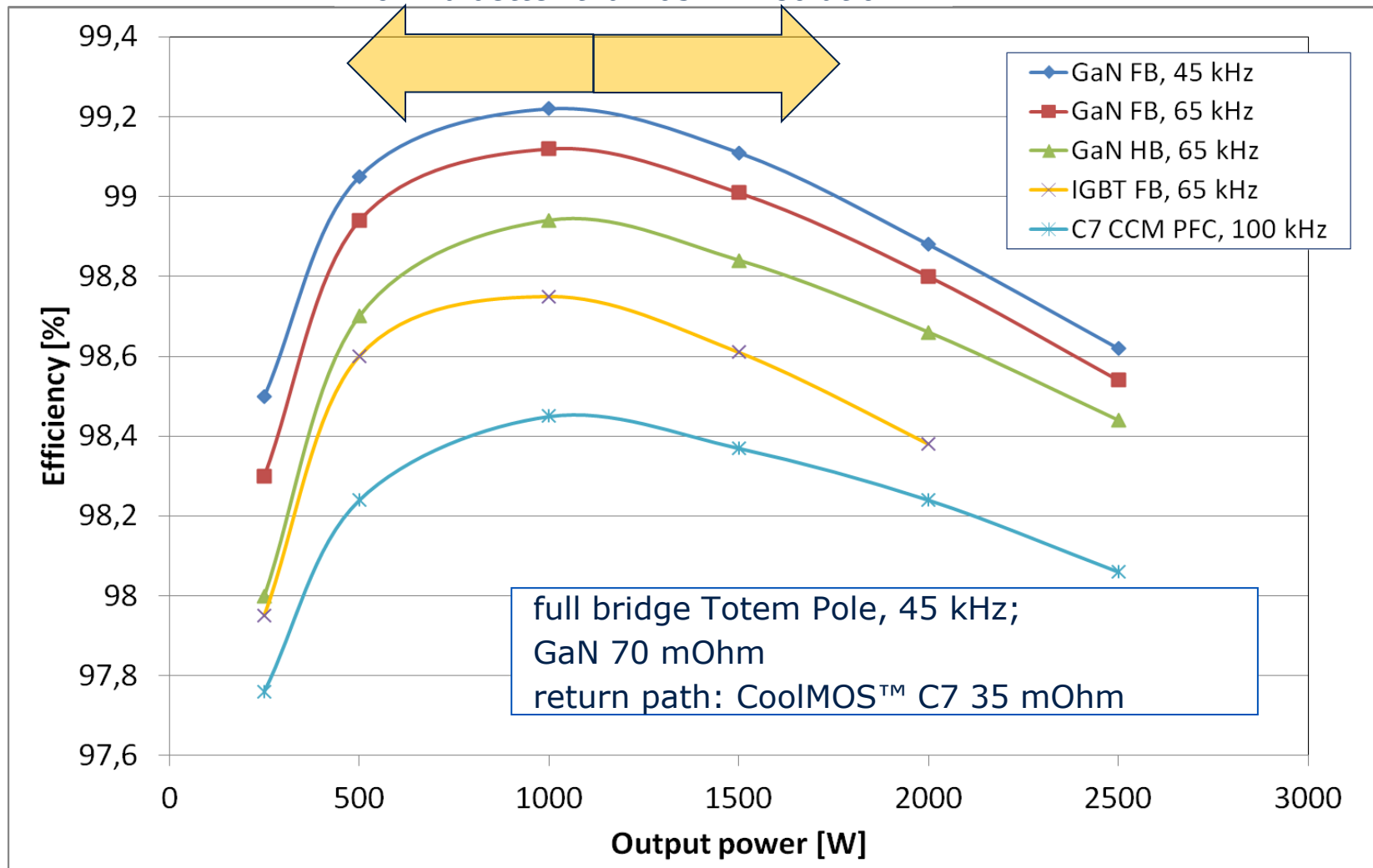


# Advantage of GaN: > 99% efficiency with combination of SJ and GaN in Totem Pole full bridge



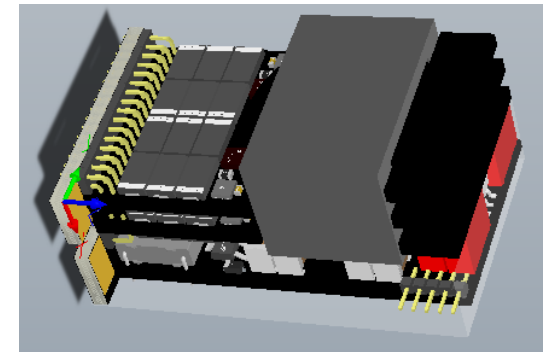
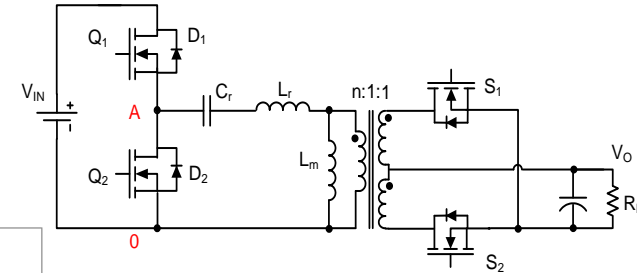
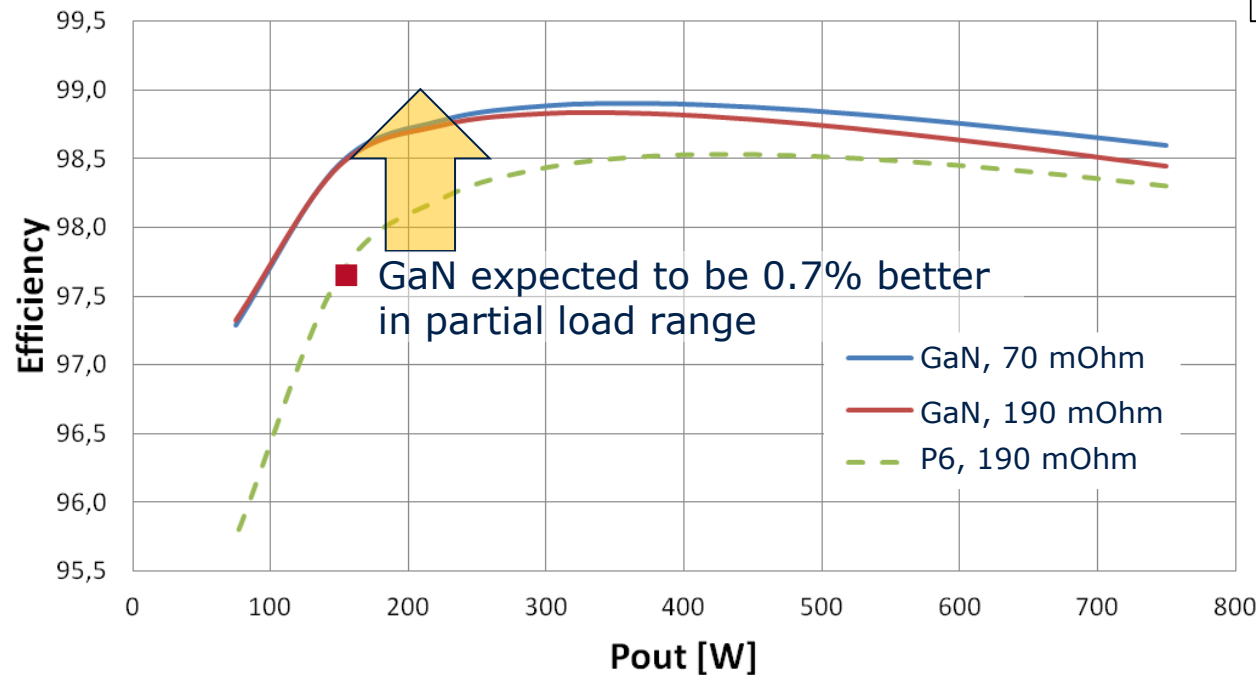
# Advantage of GaN: > 99% efficiency across wide low range with low frequency Totem Pole PFC

- >99% efficiency from 20..70% load
- 0.1% better than 65 kHz solution



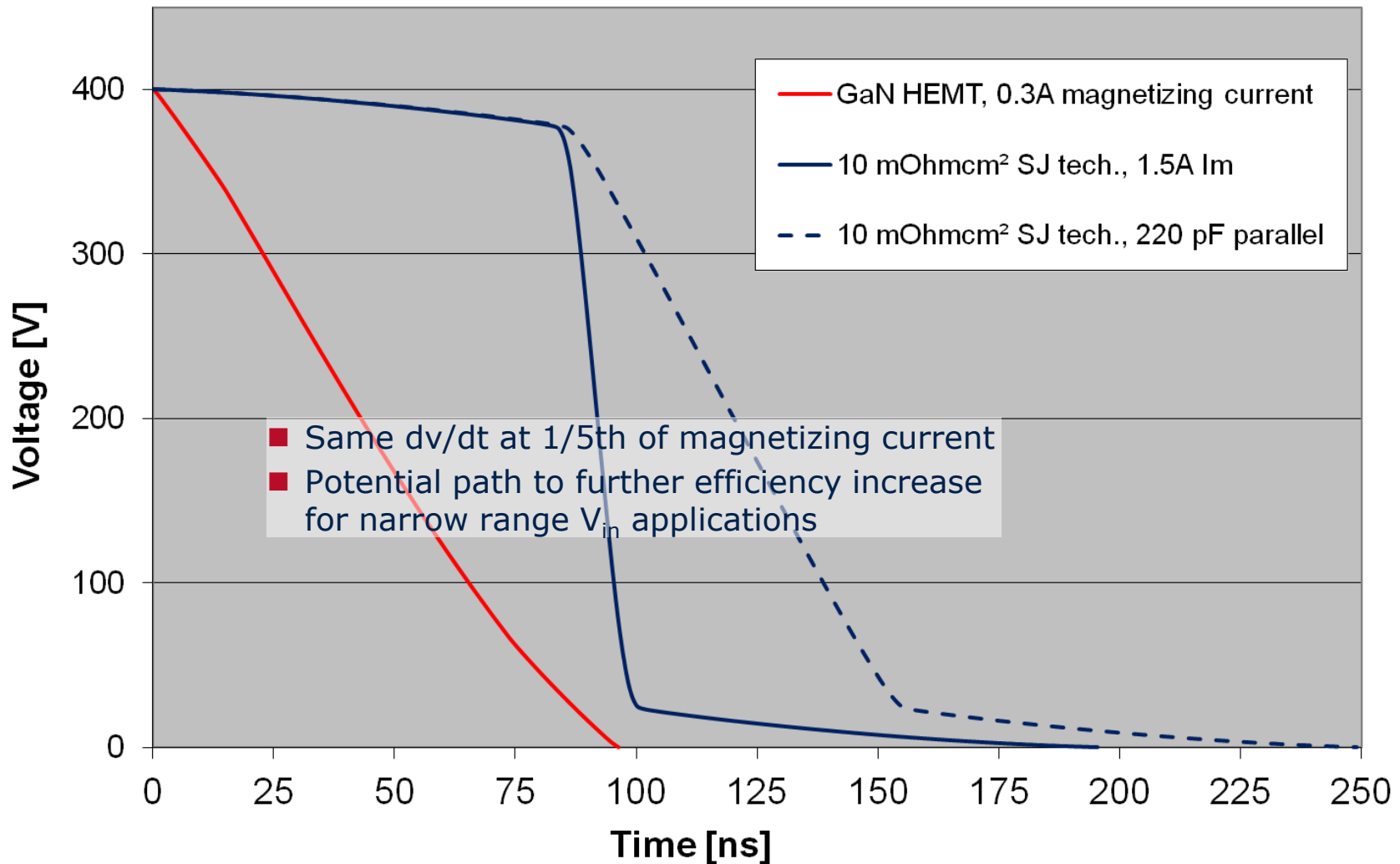
# Expected performance of GaN versus latest SJ devices

## ■ Resonant LLC DC/DC Converter (**750 W**, 400 kHz)

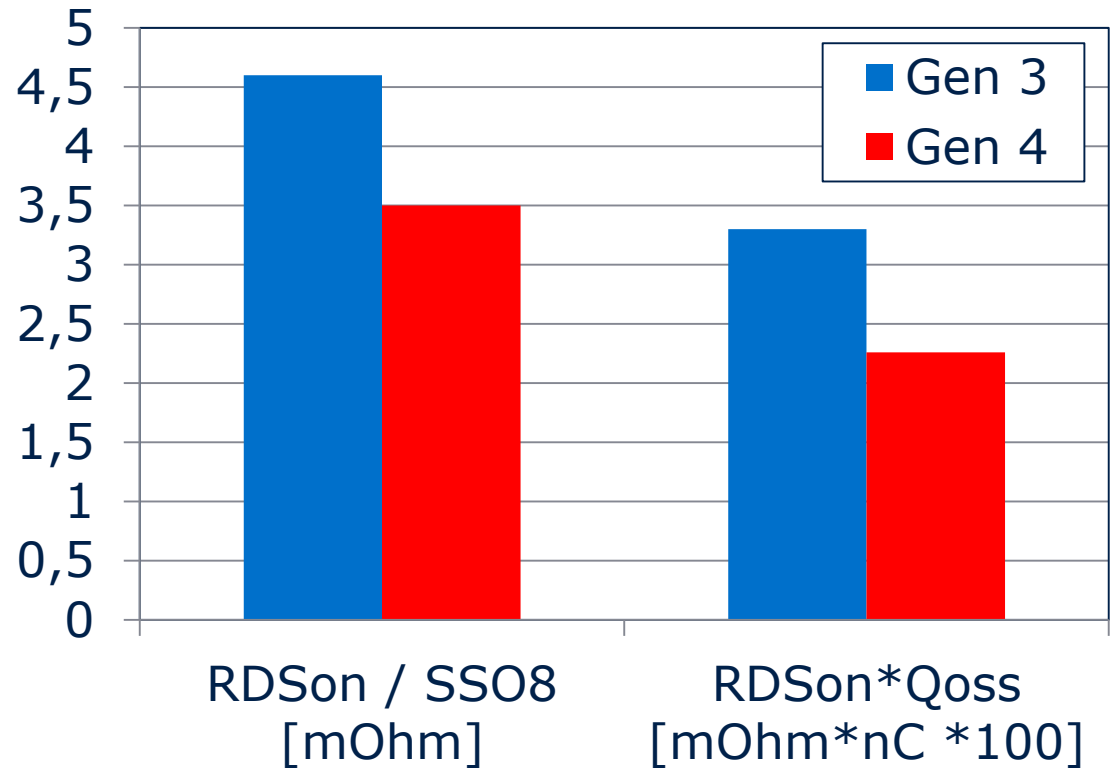
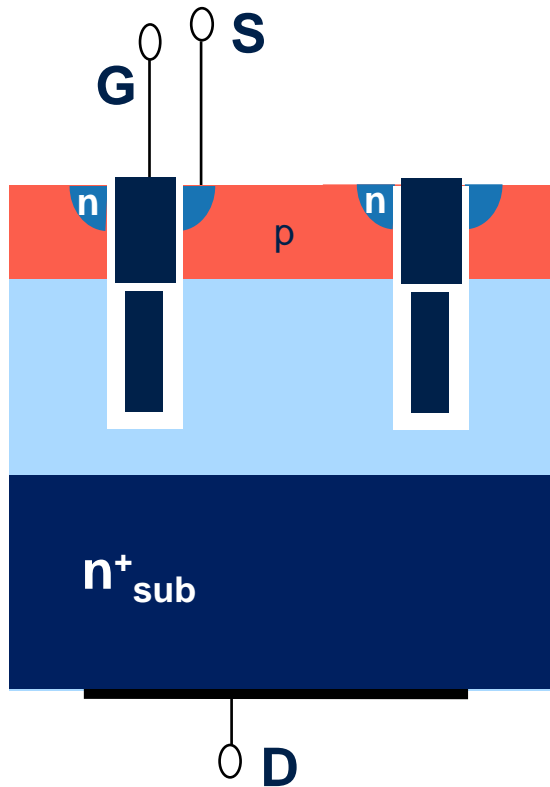


- 350V...410 V to 12 V
- Power density > 200W/in<sup>3</sup>
- Pure convection cooled

# Latest SJ devices will benefit from parallel cap to counterbalance non-linearity



# Last but not least! Recent improvements in key Figure-of-Merits for low voltage MOSFETs ...

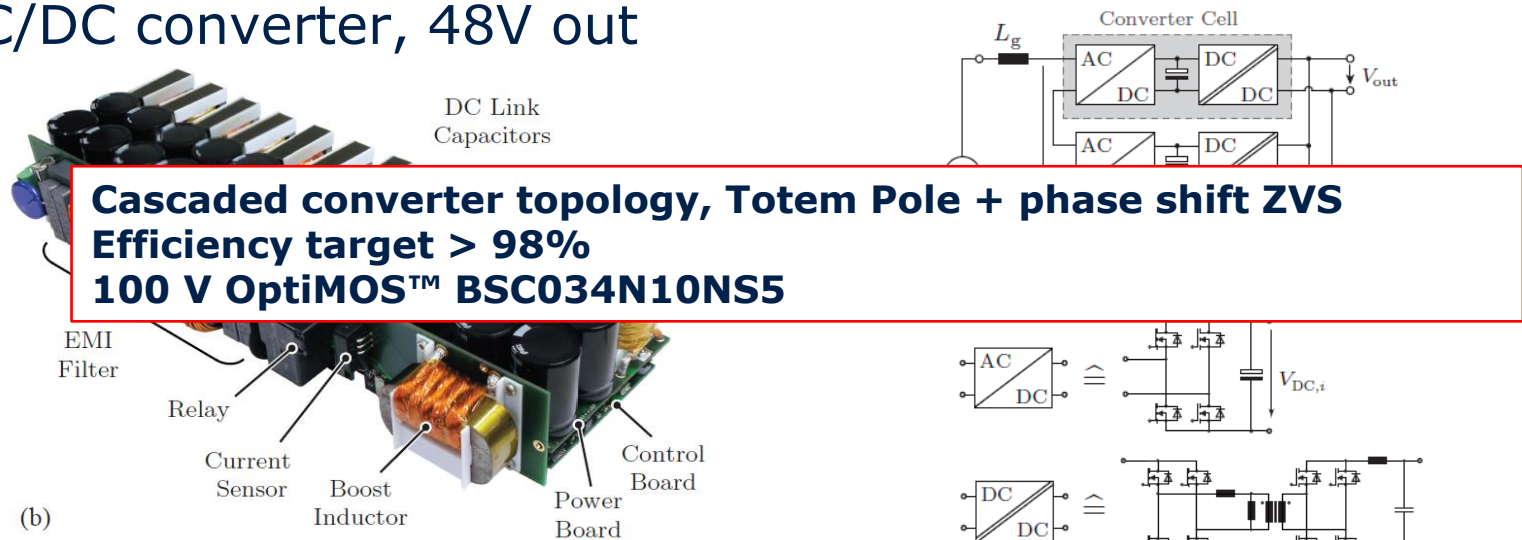


*100 V MOSFET:* smaller area-specific on-resistance and charges through further optimization of trench structure



... Allow new solutions by using cascaded multi-cell architectures!

■ 3 kW AC/DC converter, 48V out



■ FinSix 65 W Adapter, 19V out



**Switching frequency > 10 MHz**  
**200 V OptiMOS™ BSZ22DN20NS3**

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# Summary

- Superjunction devices will continue to deliver better Best-in-Class  $R_{DSon}$  devices with further improved FoM  $R_{on} * E_{oss}$
- Recent improvements in low voltage devices FoMs allow to rethink classic architectures and consider the use of LV devices in HV applications
- The use of good layout practice, transition to 4pin packages and finally to SMD packages will become more and more important and is mandatory for GaN
- GaN offers specifically advantages both in terms of power density and efficiency at hard switching topologies with continuous use of the reverse characteristic and at very high switching frequencies in resonant converters



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